Increasing superconducting transition temperature in MgB_2 by epitaxial tensile strain

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Since the discovery of superconductivity in MgB_2 by Nagamatsu *et al.* [1], many research groups have applied an exhaustive battery of techniques in an attempt to increase the transition temperature T_c , including substitution, disorder and pressure. All these efforts have failed, and the highest T_c in MgB₂ remains at about 40 K. Doping and chemical substitution in MgB_2 are difficult [2]. The few successful cases such as substitution of Mg by Al [3] and B with C [4] have so far always suppressed T_c . Although atomic disorder induced by proton irradiation enhances the pinning of vortices, it also reduces T_c [5]. Subjecting MgB₂ to pressure also causes T_c to decrease [6]. The few higher T_c values reported are from the ¹⁰B isotope effect ($T_c = 40.2$ K) [7] and by Hur *et al.* when they exposed B crystals to Mg vapor ($T_c^{onset} = 41.7$ K and zero-resistance $T_{c0} = 39.8$ K) [8]. This situation calls into question whether and how the T_c of MgB₂ can be raised. Here we show a systematic increase of T_c with epitaxial tensile strain built into MgB_2 films well beyond the bulk value (the highest $T_{c0} = 41.8$ K). Further, we identify the underlying mechanism, among several materials characteristics that determine T_c , to be the softening of the E_{2g} phonon, a possible avenue to even higher T_c .

There are two new and remarkable features of MgB₂: its high value of T_c , almost twice as high as any other intermetallic material, and that it is a clear and rather extreme example of a "two gap" superconductor which have interested theorists for decades [9–11]. This two gap character arises due to two qualitatively different Fermi surfaces (called σ and π) and their different pairing strengths (extremely strong and weak, respectively). The σ contribution is dominant, however, and specifically the contribution from the B-B stretch modes (of E_{2g} symmetry) in the B₂ graphene layer [12, 13]. Since any significant change in T_c should arise from this dominant contribution, it suffices to consider only this contribution. According to the McMillan-Allen-Dynes expression,

$$T_c \propto \omega e^{-f(\lambda,\hat{\mu})},$$
 (1)

where ω is the phonon frequency, $f(\lambda, \hat{\mu}) = (1+\lambda)/(\lambda - \hat{\mu})$, and $\hat{\mu}$ is similar to the Coulomb repulsion μ^* . The electron-phonon coupling in a multiband superconductor is a matrix, but here we only consider the maximum element $\lambda_{E_{2a}}^{\sigma\sigma}$.

$$\lambda_{E_{2g}}^{\sigma\sigma} \propto \frac{m^* |\mathcal{D}|^2}{M\omega^2},\tag{2}$$

where the σ band effective mass m^* is proportional to the density of states of holes in the σ band at the Fermi level, \mathcal{D} is the deformation potential, and M is the B mass. A change in T_c can arise from any combination of changes in ω , λ , m^* , or $\hat{\mu}$. For example, the experimentally observed suppression of T_c by Al doping can be attributed to a decrease in the σ -band hole density of states [3], and the pressure effect attributed to a decrease in λ accompanied by an increase in the E_{2q} phonon frequency [14].

The epitaxial MgB₂ films in this work were deposited by a hybrid physical-chemical vapor deposition (HPCVD) technique [15]. Pure magnesium chips were heated simultaneously with the substrate to 720°C to generate a high Mg pressure, and 1000 ppm diborane (B₂H₆) in H₂ was used as the B precursor. The carrier gas was a H₂ flow of 450 sccm at a pressure of 100 Torr. The films were deposited on both (0001) 4H-SiC and (0001) sapphire substrates. We have shown previously that films on (0001) SiC are *c*-axis oriented and epitaxial with an in-plane alignment of the *a*-axis of MgB₂ with that of SiC [16]. Films on (0001) sapphire are also *c*-axis oriented and epitaxial, but the *a*-axis of MgB₂ is rotated by 30° in-plane from the *a*-axis of sapphire [15]. Because of the highly reducing H₂ ambient during the deposition and the high purity source of B from B₂H₆, the HPCVD technique produces very clean MgB₂ thin films with a residual resistivity at T_c as low as 0.26 $\mu\Omega$ cm [17].

We have reported previously that the properties of MgB₂ films on (0001) SiC depend on film thickness [17]. We found that a similar dependence also exists for films on (0001) sapphire substrates. Figure 1(a) shows resistivity versus temperature curves for MgB₂ films with different thicknesses grown on sapphire substrates, and Fig. 1(b) shows the curves for films on SiC substrates. The figures clearly show that most samples here have T_{c0} above 40 K, considerably higher than that of the bulk MgB₂. Further, T_c becomes higher as the film thickness increases. The thickness dependence of the zero-resistance T_{c0} for both substrates is plotted in Fig. 1(c). A clear trend of increasing T_{c0} with film thickness is seen for both substrates with T_{c0} consistently 1 - 1.5 degree higher in films on SiC than on sapphire. The highest T_{c0} was observed in a 3400 Å thick MgB₂ film on a SiC substrate with $T_{c0} = 41.8$ K, about two degrees higher than all previously-reported values.

X-ray diffraction analysis shows a direct correlation between the lattice constants of the films, indicating biaxial strain, and T_{c0} . From $\theta - 2\theta$ scans we measured the *c*-axis lattice constants, and in conjunction with ϕ scans of asymmetric reflections we determined the *a*-axis lattice constants. Figure 2 shows (a) the *a*-axis and (b) the *c*-axis lattice constants of

several MgB₂ films of different thicknesses and different T_{c0} 's. Despite the large error bars, we clearly see that a higher T_{c0} corresponds to a larger *a*-axis lattice constant and a smaller *c*-axis lattice constant. More strikingly, although the results on SiC and sapphire follow two different T_{c0} versus thickness curves in Fig. 1(c), they fall on same T_{c0} versus lattice constant curves in Fig. 2, indicating that strain is the determining factor for T_{c0} . Compared to the bulk lattice constants of a = 3.086 Å and c = 3.524 Å [1], it is evident that the tensile strain in the films causes T_{c0} to increase beyond the bulk value, and the thicker the films the larger the tensile strain.

An increase of tensile strain with film thickness has been observed in films grown in the Volmer-Weber mode: film growth by initial nucleation of discrete islands which later coalesce [18, 19]. When the islands coalesce, they "zip up" because the surface energy of the islands is larger than the free energy of the grain boundaries, thus creating a tensile strain which increases with film thickness [20]. In the so-called "low-mobility" films, the height of the zipped boundary is less than the film thickness when the islands coalesce, and the "zipping-up" continues at the surface terrace level long afterwards [21]. Therefore, the tensile strain continues to increase with film thickness toward the upper bound value predicted by the Nix model [20]. The coalescence tensile strain has been suggested for GaN, a wide-band-gap compound semiconductor with a similar crystal structure to MgB_2 [22]. Atomic force microscopy (AFM) images of two MgB_2 films on SiC, one of 75 Å and the other of 900 Å, shown in Fig. 3(a) and 3(b), respectively, confirm that MgB₂ films grow in the Volmer-Weber mode. Hexagonal-shaped MgB_2 crystallites are seen in the thinner film, which coalesce into a continuous film at larger film thickness. The continued increase of tensile strain beyond coalescence and the surface terraces that are readily observable in thicker films indicate that MgB_2 behaves like a low-mobility system at 720°C. This is consistent with the high melting temperature of B (2075° C) or MgB₂ (it melts congruently at 2430 °C with pressure higher than 49000 Torr [23]). The grain growth as the film becomes thicker may also contribute to the tensile strain as the reduction of the defect density can generate a tensile strain in the film on the top [24]. Indeed the defect density is high near the MgB_2/SiC substrate interface and decreases as the film thickness increases, as shown by the cross-sectional transmission electron microscopy (TEM) images in Fig. 3(c) (low magnification) and 3(d) (high resolution).

The magnitudes of the tensile strain are different on SiC and sapphire substrates, reflect-

ing the differences in the lattice mismatch and thermal expansion mismatch. The in-plane lattice constant is a = 3.07 Å for 4H-SiC and a = 4.765 Å for sapphire, and thus the lattice mismatch could result in a much larger compressive strain for sapphire (11% compressive with the 30° in-plane rotation) than for SiC (0.1% compressive). The coefficient of thermal expansion at room temperature is 5.5×10^{-6} K⁻¹ for MgB₂ [25], 3.0×10^{-6} K⁻¹ for SiC [26], and 6.7×10^{-6} K⁻¹ for sapphire [27]. Therefore, the thermal expansion mismatch will lead to a tensile strain in films on SiC, and a compressive strain in films on sapphire when the film is cooled from the deposition temperature. These factors are combined with the tensile growth strain to determine that there is a larger tensile strain in the MgB₂ films grown on SiC substrates.

The systematic increase of T_c with tensile strain shown in Fig. 2 allows us to investigate possible approaches to raise the T_c of MgB₂. For this purpose we have carried out firstprinciples calculations using the experimental lattice constants for the highest T_c sample in Fig. 2, which are $\Delta a/a = +0.55\%$ and $\Delta c/c = -0.25\%$. We found that this leads to a decrease in the σ hole concentration, $\Delta m^*/m^* = -1.2\%$, and $2\Delta |\mathcal{D}|/|\mathcal{D}| = -2.6\%$. The calculated change in the E_{2g} phonon frequency is in agreement with the experimentally extrapolated value from the polycrystalline sample of $\Delta \omega/\omega = -5.5\%$ [14]. From these values and using Eq. (2), we obtain

$$\frac{\Delta\lambda_{E_{2g}}^{\sigma\sigma}}{\lambda_{E_{2g}}^{\sigma\sigma}} = \frac{\Delta m^*}{m^*} + 2\frac{\Delta|\mathcal{D}|}{|\mathcal{D}|} - 2\frac{\Delta\omega}{\omega} = -1.2\% - 2.6\% + 11\% \approx +7\%.$$
(3)

From Eq. (1) and using as representative numbers, $\lambda = \lambda_{\sigma} + \lambda_{\pi} = 0.9 + 0.2 = 1.1$, and $\hat{\mu} = 0.2$:

$$\frac{\Delta T_c}{T_c} = \frac{\Delta \omega}{\omega} - \Delta f = \frac{\Delta \omega}{\omega} + \frac{1 + \hat{\mu}}{(\lambda - \hat{\mu})^2} \Delta \lambda = -5.5\% + 10.4\% \approx +5\%.$$
(4)

This value is quite close to the experimental enhancement of T_c . This analysis identifies the underlying mechanism of the tensile-strain-induced increase in T_c as the softening of the E_{2g} bond-stretching mode. The decrease in the E_{2g} phonon frequency leads to the large relative increase in the σ band coupling strength (7%), which more than compensates the lowering of the temperature/energy scale governed by ω (and as mentioned, decreases by 5%). The result is also consistent with a previous first-principles calculation by Yildirim and Gülseren on the pressure effects in MgB₂ [28].

As a check on the validity of the theoretical calculations, we have measured the E_{2g} phonon frequencies of MgB₂ films of different thicknesses by Raman scattering. Raman spectra were taken using a SPEX Triplemate spectrometer in backscattering geometry with the 514.5 nm Ar⁺ laser line as the excitation source. Figure 4 shows the spectra of two films: a 3400 Å-thick film on SiC and a 800 Å-thick film on sapphire. The thicker film on SiC has larger tensile strain than the thinner film on sapphire, and consequently has a higher T_{c0} as compared to the film on sapphire. The broad peak around 600 cm⁻¹ has been assigned to the E_{2g} mode [14]. Although the peak is broad, a clear difference between the peak energies for the two films is seen. The higher T_c film on SiC has a softer E_{2g} mode than the lower T_c film on sapphire by about 20 cm⁻¹, i.e 3.3%.

There have been reports of reduced T_c in MgB₂ whereby a lower T_c corresponds to a higher E_{2g} phonon frequency [14, 29]. We show here that lowering the E_{2g} phonon frequency can increase T_c to above the bulk value. In our work, this was accomplished by the tensile strain built into the films during the HPCVD growth process, and the E_{2g} phonon softening is about 5.5%. An inspection of Eqns. (3) and (4) shows that if one can reduce the E_{2g} phonon frequency further, the T_c of MgB₂ will increase more than what we have shown here.

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REFERENCES

- Nagamatsu, J., Nakagawa, N., Muranaka, T., Zenitani, Y. & Akimitsu, J. Superconductivity at 39 K in magnesium diboride. *Nature (London)* 410, 63–64 (2001).
- [2] Cava, R. J., Zandbergen, H. W. & Inumaru, K. The substitutional chemistry of MgB₂. *Physica* C 385, 8–15 (2003).
- [3] Slusky, J. S. et al.. Loss of superconductivity with the addition of Al to MgB₂ and a structural transition in Mg_{1-x}Al_xB₂. Nature (London) 410, 343–345 (2001).
- [4] Lee, S., Masui, T., Yamamoto, A., Uchiyama, H. & Tajima, S. Carbon-substituted MgB₂ single crystals. *Physica C* 397, 7–13 (2003).
- [5] Bugoslavsky, Y., Perkins, G. K., Qi, X., Cohen, L. F. & Caplin, A. D. Vortex dynamics in superconducting MgB₂ and prospects for applications. *Nature (London)* 410, 563–565 (2001).
- [6] Monteverde, M. et al.. Pressure dependence of the superconducting transition temperature of magnesium diboride. Science 292, 75–77 (2001).
- [7] Hinks, D. G., Claus, H. & Jorgensen, J. D. The complex nature of superconductivity in MgB₂ as revealed by the reduced total isotope effect. *Nature (London)* 411, 457–460 (2001).
- [8] Hur, N. et al.. High-quality MgB₂ films on boron crystals with onset T_c of 41.7 K. Appl. Phys. Lett. 79, 4180–4182 (2001).
- [9] Choi, H. J., Roundy, D., Sun, H., Cohen, M. L. & Louie, S. G. The origin of the anomalous superconducting properties of MgB₂. *Nature (London)* 418, 758–760 (2002).
- [10] Pickett, W. Mind the double gap. *Nature (London)* 418, 733–734 (2002).
- [11] Souma, S. et al.. The origin of multiple superconducting gaps in MgB₂. Nature (London) 423, 65–67 (2003).
- [12] Liu, A. Y., Mazin, I. I. & Kortus, J. Beyond Eliashberg superconductivity in MgB₂: Anharmonicity, two-phonon scattering, and multiple gaps. *Phys. Rev. Lett.* 87, 087005 (2001).
- [13] An, J. M. & Pickett, W. E. Superconductivity of MgB₂: Covalent bonds driven metallic. *Phys. Rev. Lett.* 86, 4366–4369 (2001).
- [14] Goncharov, A. F. & Struzhkin, V. V. Pressure dependence of the Raman spectrum, lattice parameters and superconducting critical temperature of MgB₂: evidence for pressure-driven phonon-assisted electronic topological transition. *Physica C* 385, 117–130 (2003).

- [15] Zeng, X. H. et al.. In situ epitaxial MgB₂ thin films for superconducting electronics. Nature Materials 1, 35–38 (2002).
- [16] Zeng, X. H. et al.. Superconducting MgB₂ thin films on silicon carbide substrates by hybrid physical-chemical vapor deposition. Appl. Phys. Lett. 82, 2097–2099 (2003).
- [17] Pogrebnyakov, A. V. et al.. Thickness dependence of the properties of epitaxial MgB₂ thin films grown by hybrid physical-chemical vapor deposition. Appl. Phys. Lett. 82, 4319–4321 (2003).
- [18] Floro, J. A., Chason, E., Cammarata, R. C. & Srolovitz, D. J. Physical origins of intrinsic stresses in Volmer-Weber thin films. *MRS Bulletin* 27(1), 19–25 (2002).
- [19] Koch, R. The intrinsic stress of polycrystalline and epitaxial thin metal films. J. Phys.: Condens. Matter 6, 9519–9550 (1994).
- [20] Nix, W. D. & Clemens, B. M. Crystallite coalescence: A mechanism for intrinsic tensile stresses in thin films. J. Mater. Res. 14, 3467–3473 (1999).
- [21] Sheldon, B. W., Lau, K. H. A. & Rajamani, A. Intrinsic stress, island coalescence, and surface roughness during the growth of polycrystalline films. J. Appl. Phys. 90, 5097–5103 (2001).
- [22] Etzkorn, E. V. & Clarke, D. R. Cracking of GaN films. J. Appl. Phys. 89, 1025–1034 (2001).
- [23] Liu, Z. K., Schlom, D. G., Li, Q. & Xi, X. X. Thermodynamics of the Mg-B system: Implications for the deposition of MgB₂ thin films. *Appl. Phys. Lett.* 78, 3678–3680 (2001).
- [24] Chaudhari, P. Grain growth and stress relief in thin films. J. Vac. Sci. Technol. 9, 520–522 (1972).
- [25] Buzea, C. & Yamashita, T. Review of superconducting properties of MgB₂. Supercond. Sci. Tech. 14, R115–46 (2001).
- [26] Li, Z. & Brandt, R. Thermal expansion of the hexagonal (6H) polytype of silicon carbide. J. Amer. Chem. Soc. 69, 863–866 (1986).
- [27] Touloukian, Y. S., Kirby, R. K., Taylor, R. E. & Lee, T. Y. R. Thermophysical Properties of Matter, vol. 13 (Plenum, New York, 1977).
- [28] Yildirim, T. & Gülseren, O. A simple theory of 40 K superconductivity in MgB₂: first-principles calculations of T_c, its dependence on boron mass and pressure. J. Phys. Chem. Sol. 63, 2201–2206 (2002).
- [29] Masui, T., Lee, S. & Tajima, S. Carbon-substitution effect on the electronic properties of MgB₂ single crystals. *cond-mat/0312458* (2003).

FIGURE CAPTIONS

FIG. 1: Superconducting transition in MgB₂ films of different thicknesses. The resistivity versus temperature curves for films on (a) (0001) sapphire and (b) (0001) SiC substrates show that T_c increases and resistivity decreases as the film becomes thicker on both substrates. (c) Zero-resistance T_{c0} as a function of film thickness on both sapphire and SiC substrates. Similar increases with film thickness are seen for both substrates, although T_{c0} is one degree higher in films on SiC.

FIG. 2: Dependence of T_{c0} on film strain as determined by x-ray diffraction. (a) T_{c0} versus *a*-axis lattice constants. (b) T_{c0} versus *c*-axis lattice constants. The error bars indicate the accuracy of the measurement. The MgB₂ films on both sapphire and SiC substrates follow the same curves. Among data from the same substrate, a higher T_{c0} corresponds to a thicker film. As a comparison, the bulk lattice constants of MgB₂ are a = 3.086 Å and c = 3.524 Å.

FIG. 3: Growth mode and microstructure of MgB₂ films. (a) AFM image of a 75 Å-thick film. (b) AFM image of a 900 Å-thick film. Both films were grown on (0001) SiC substrates at 720°C with a B₂H₆ gas mixture flow rate of 50 sccm. Hexagonal-shaped MgB₂ crystallites seen in the thinner film coalesce into a continuous film at larger thickness. (c) Low-magnification and (d) high-resolution cross-section TEM images of a 2100 Å-thick MgB₂ film on (0001) SiC taken along the [1100] direction. Both show that the defect density is high near the film/substrate interface and decreases as the film thickness increases. The dotted line in (d) indicates the MgB₂/SiC interface and the small arrows show the lattice deformation due to dislocations, most of which have Burgers vectors \mathbf{b} =[0001].

FIG. 4: Dependence of E_{2g} phonon frequency on film strain. The figure shows Raman spectra of two films: 3400 Å-thick on SiC and 800 Å-thick on sapphire. The thicker film on SiC has larger tensile strain and a higher T_{c0} than the thinner film on sapphire. The Raman result shows that the E_{2g} phonon in it has a lower frequency.



Fig. 1 (a) and (b) Pogrebnyakov et al.



Fig. 1 (c) Pogrebnyakov et al.



Fig. 2 (a) and (b) Pogrebnyakov et al.



(b)



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Fig. 3 (a) and (b) Pogrebnyakov et al.

Fig. 3 (c) and (d) Pogrebnyakov et al.



(d)



